

# Nd-doped aluminum oxide integrated amplifiers at 880 nm, 1060 nm, and 1330 nm

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**Abstract**—Neodymium-doped  $\text{Al}_2\text{O}_3$  layers were deposited on thermally oxidized Si substrates and channel waveguides were patterned using reactive-ion etching. Internal net gain on the  $\text{Nd}^{3+}$  transitions at 880, 1064, and 1330 nm was investigated, yielding a maximum gain of 6.3 dB/cm at 1064 nm. Values for the energy-transfer upconversion parameter for different  $\text{Nd}^{3+}$  concentrations were deduced.

**Keywords**—Neodymium, aluminum oxide, channel waveguide, optical amplifiers, energy-transfer upconversion

## I. INTRODUCTION

Integrated optical channel waveguides doped with rare-earth ions have been subject to investigations over the last two decades. Various host materials and different waveguide fabrication techniques have been employed to demonstrate gain in Nd-doped channel waveguides [1-4] and lasers [5,6]. Amorphous aluminum oxide is an excellent host for rare-earth ions, having low optical loss and high refractive index [7,8]. The latter allows for small bending radii and correspondingly small on-chip devices. In this work, optical gain in  $\text{Al}_2\text{O}_3:\text{Nd}^{3+}$  is investigated at 880, 1064, and 1330 nm. We report a maximum gain of 6.3 dB/cm for the transition at 1064 nm. In addition, internal net gain is reported for 880 and 1330 nm. Values of the energy-transfer upconversion (ETU) parameter were obtained from the measured gain by simulations.

## II. CHANNEL WAVEGUIDE FABRICATION

$\text{Al}_2\text{O}_3:\text{Nd}$  layers with a thickness of 600 nm were reactively co-sputtered onto thermally oxidized 10-cm Si wafers. Al and Nd targets of high purity were sputtered using Ar guns, while oxygen was supplied as a gas. By varying the Nd-target power, different  $\text{Nd}^{3+}$  concentrations from  $0.65 \times 10^{20} \text{ cm}^{-3}$  to  $2.95 \times 10^{20} \text{ cm}^{-3}$  have been obtained. The dopant concentrations were confirmed by Rutherford Backscattering Spectroscopy (RBS). Straight channel waveguides with a width of 2.0  $\mu\text{m}$  were fabricated in the layers by means of reactive ion etching (RIE). The channels were shallow etched by 70 nm. These channels are single-mode at a wavelength of 1064 nm and multi-mode at the pump wavelength of 802 nm. The channel waveguides use air as the cladding.

## III. EXPERIMENTAL RESULTS

The luminescence spectrum of Fig. 1 was obtained by pumping the  $\text{Nd}^{3+}$  ions at 802 nm from the  $^4\text{I}_{9/2}$  ground level into the  $^5\text{F}_{5/2}$  level and collecting light from the waveguide top into a spectrophotometer (Jobin Yvon iHR550). The obtained luminescence spectrum was corrected for the response of the used InGaAs detector. The measured  $^4\text{F}_{3/2} \rightarrow ^4\text{I}_{11/2}$  luminescence at 1064 nm is approximately five times stronger than the  $^4\text{F}_{3/2} \rightarrow ^4\text{I}_{9/2}$  and  $^4\text{F}_{3/2} \rightarrow ^4\text{I}_{13/2}$  luminescence at 880 nm and 1340 nm, respectively. The luminescence at 1330 nm has a value equaling 75% of the peak value at 1340 nm.

Small-signal internal net gain investigations were performed using a pump-probe method. A Ti:Sapphire laser (Spectra-Physics 3900s) was employed as the pump source at 802 nm, while diode lasers at 880 nm and 1330 nm and a Nd:Yag laser at 1064 nm were employed as signal sources. Attenuation of the signal to a power of 1-10  $\mu\text{W}$  ensured operation in the small-signal regime. Signal light modulated by a mechanical chopper and pump light were combined via a dichroic mirror and coupled into and out of the waveguides using high-numerical-aperture (0.85 and 0.4 NA, resp.) microscope objectives. The unabsorbed pump light was filtered from the signal light using a high-pass filter at 850 nm placed behind the outcoupling objective, while the signal light was measured by a Germanium detector and amplified by a lock-in amplifier connected to the chopper. The optical gain was determined by measuring the ratio of the transmitted intensities in the pumped and unpumped case,  $I_p$  and  $I_u$ , respectively. The internal net gain per unit length was obtained by dividing by the sample length  $l$  and subtracting the combined measured propagation and absorption losses ( $\alpha$ ):

$$g_{\text{meas}}(l) = 10 \cdot \log_{10}(I_p(l)/I_u(l))/l - \alpha(l) \quad (1)$$

Figure 2a shows the measured internal net gain per unit length as a function of  $\text{Nd}^{3+}$  concentration at a launched power of 45 mW. At a concentration of  $1.68 \times 10^{20} \text{ cm}^{-3}$ , a maximum optical gain of 6.3 dB/cm and 1.93 dB/cm was found at 1064 and 1330 nm, respectively. At a concentration of  $1.40 \times 10^{20} \text{ cm}^{-3}$ , a maximum of 1.57 dB/cm was found at 880 nm.

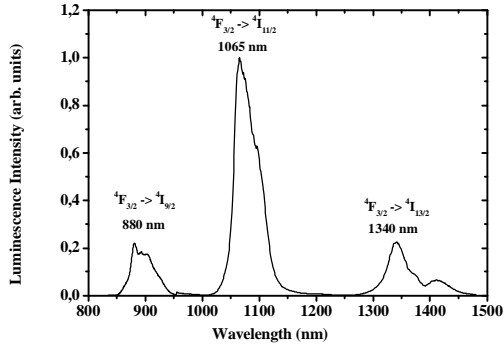


Figure 1. Broadband luminescence spectrum of a  $\text{Al}_2\text{O}_3:\text{Nd}$  channel waveguide

The internal net gain per unit length at these optimum concentrations as a function of launched power is displayed in Fig 2b. Both the decrease in gain per unit length as a function of  $\text{Nd}^{3+}$  concentration in Fig. 2a and the gain saturation visible in Fig. 2b are mainly attributed to energy-transfer upconversion (ETU) processes from the  $^4\text{F}_{3/2}$  level into higher-lying energy levels [9,10].

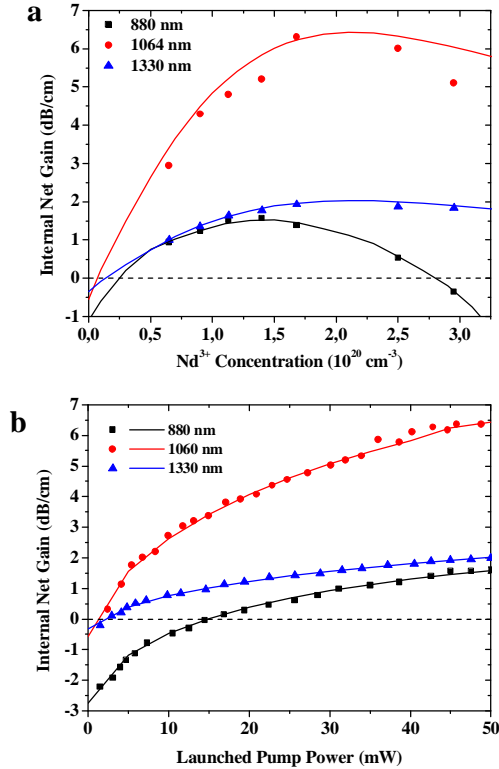


Figure 2. Measured (dots) and calculated (lines) internal net gain per unit length at 880, 1064 and 1330 nm versus (a)  $\text{Nd}^{3+}$  concentration for a launched power of 45 mW and (b) launched pump power for the samples with maximum gain per unit length in (a)

#### IV. GAIN SIMULATIONS

The optical gain in Fig. 2 was simulated by numerically solving a rate-equation model using the ETU parameter as a fitting parameter to the experimentally obtained gain. The simplified rate-equation model describing the population mechanisms of the  $\text{Nd}^{3+}$  system can be described as follows:

$$dN_4 / dt = R_{05} - R_{4i} - R_{04} - \tau_4^{-1} N_4 - W_{ETU} N_4^2 \quad (2)$$

$$N_0 = N_d - N_4 \quad (3)$$

where  $N_4$  and  $\tau_4$  are the population density and lifetime of the  $^4\text{F}_{3/2}$  level, respectively,  $N_0$  is the ground-state population and  $N_d$  is the dopant concentration.  $W_{ETU}$  is the combined upconversion coefficient of three ETU processes originating in the metastable  $^4\text{F}_{3/2}$  level [9,10]. The pump absorption rate from the  $^4\text{I}_{9/2}$  ground-state into  $^4\text{F}_{5/2}$  is expressed by  $R_{05}$ , stimulated emission from  $^4\text{F}_{3/2}$  into the lower-lying levels  $i = 0, 1, \text{ and } 2$  for 880 nm, 1064 nm, and 1330 nm, respectively, by  $R_{4i}$ , and reabsorption from the ground state into  $^4\text{F}_{3/2}$  by  $R_{04}$  (taken into account only for the 3-level transition at 880 nm). The values for the ETU parameter at 1064 nm thus obtained are 0.51, 0.89, 1.32, and  $2.32 \times 10^{-16} \text{ cm}^3 \text{ s}^{-1}$  for  $\text{Nd}^{3+}$  concentrations of 0.65, 1.13, 1.68, and  $2.95 \times 10^{20} \text{ cm}^{-3}$ , respectively.

#### V. CONCLUSIONS

$\text{Al}_2\text{O}_3:\text{Nd}^{3+}$  layers have been deposited onto thermally oxidized Si substrates and single-mode channel waveguides have been fabricated. A maximum small-signal gain of 1.57 dB/cm, 1.93 dB/cm, and 6.3 dB/cm at 880, 1330, and 1064 nm, respectively, was obtained. By fitting the simulated to the measured gain, values for the ETU parameter in  $\text{Al}_2\text{O}_3:\text{Nd}^{3+}$  at four different  $\text{Nd}^{3+}$  concentrations have been obtained.

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